

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of

Jae-Jong HAN, et al.

Serial No.

[Division of Serial No. 10/277,801, filed October 23, 2002]

Filed: March 22, 2004

For: PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION APPARATUS AND
METHOD FOR FORMING NITRIDE LAYER USING THE SAME

PRELIMINARY AMENDMENT

Commissioner for Patents
Alexandria, VA 22313-1450

Sir:

Prior to calculation of the statutory filing fee, kindly amend the application identified above as follows:

IN THE CLAIMS

Cancel Claims 1-7 without prejudice or disclaimer.

Following is a listing of claims, which listing supersedes all previously presented claims.